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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/080,104	02/21/2002	Каоги Коіке	09792909-5344	1692	
26263	7590 09/21/2006		EXAMINER		
SONNENS P.O. BOX 06	CHEIN NATH & ROS 51080	ERDEM,	ERDEM, FAZLI		
WACKER DRIVE STATION, SEARS TOWER CHICAGO, IL 60606-1080			ART UNIT	PAPER NUMBER	
			2826		
				DATE MAIL ED: 09/21/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

•	Application No.	Applicant(s)
	10/080,104	KOIKE ET AL.
Office Action Summary	Examiner	Art Unit
	Fazli Erdem	2826
The MAILING DATE of this communication appe Period for Reply	ears on the cover sheet with the c	orrespondence address
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	TE OF THIS COMMUNICATION 6(a). In no event, however, may a reply be tim ill apply and will expire SIX (6) MONTHS from to cause the application to become ABANDONED	l. ely filed the mailing date of this communication. 0 (35 U.S.C. § 133).
Status		·
1) ☐ Responsive to communication(s) filed on <u>06 Ju</u> 2a) ☐ This action is FINAL . 2b) ☐ This 3) ☐ Since this application is in condition for allowan closed in accordance with the practice under Expression is the practice of the p	action is non-final. ce except for formal matters, pro	
Disposition of Claims		
4)	n from consideration. /are allowed.	·
Application Papers		
9) The specification is objected to by the Examiner 10) The drawing(s) filed on is/are: a) access Applicant may not request that any objection to the or Replacement drawing sheet(s) including the correction in the original or declaration is objected to by the Examiner	epted or b) objected to by the E drawing(s) be held in abeyance. See on is required if the drawing(s) is obj	ected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list of	s have been received. s have been received in Application ity documents have been receive (PCT Rule 17.2(a)).	on No d in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal Pa	te

DETAILED ACTION

Allowable Subject Matter

1. Claims 23-37, 51-57, 61-65 and 69-82 and 84-86 allowed.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claim 66 and 68 rejected under 35 U.S.C. 103(a) as being unpatentable over Yahiro et al. (6,204,509) in view of Mitome et al. (5,695,897) further in view of Magome (6,265,119)

Regarding Claim 66 and 68, Yahiro et al. disclose a projection-microlithography apparatus, masks, and related method incorporating reticle distortion measurement and correction where in figs. 1(a) – 1(f), it is disclosed a plurality of pattern formation regions 50 in which mask circuit patterns are to be formed, and a supporting region 51 in which an y mask circuit is not to be formed where the supporting region being provided for holding plurality of pattern formation regions while separating plurality of pattern formation regions from each other where the supporting region has first alignment marks 53 used at the time of alignment of a mask made from the mask making member for forming the mask circuit pattern and second alignment patterns 301 used at the time of alignment of a substrate to be exposed for forming circuit patterns. Furthermore, Yahiro et al. disclose that first and second alignment marks are formed on an electron scatterer formed on a membrane by selectively removing electron scatterer and first and second

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alignment marks formed on a mask board. Yahiro et al. fail to disclose that first and second alignment marks formed one at a time and the required burying of the contact hole and the required type of exposure system. However, Mitome et al. disclose an alignment method and semiconductor exposure method where in claims 1 and 2, the required one at a time alignment mark method is disclosed. Furthermore, Magome discloses a method for producing semiconductor devices where in columns 2 and 8 the required exposure system type is disclosed.

It would have been obvious to one of having ordinary skill in the art at the time the invention was made to include the required one at a time alignment mark method and the required full exposure system in Yahiro et al. as taught by Mitome et al. in order to have a mask making member with increased reliability and higher resolution.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fazli Erdem whose telephone number is (571) 272-1914. The examiner can normally be reached on M - F 8:00 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (571) 272-1915. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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FE September 17, 2006

PRIMARY EXAMINER